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(54) **Title:** BACKSIDE GAS LEAKBY FOR BEVEL DEPOSITION REDUCTION

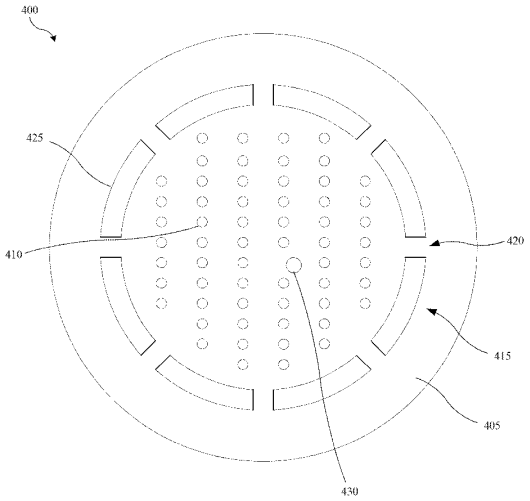

FIG. 4

(57) **Abstract:** Exemplary substrate support assemblies include an electrostatic chuck body defining a substrate platform. The substrate platform may be characterized by an upper surface. The platform may define a purge aperture. The platform may include a plurality of mesas that are disposed in an inner region of the upper surface. Each of the mesas may protrude upward from the upper surface. The platform may include a sealing band that extends upward from the upper surface in a circumferential pattern and partially encircles the inner region of the upper surface. Top surfaces of the mesas and sealing band may form a support surface for a substrate. The sealing band may define a number of gaps. The assemblies may include a support stem coupled with the electrostatic chuck body, a heater embedded within the electrostatic chuck body, and a backside gas source that is coupled with the purge aperture of the support surface.

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